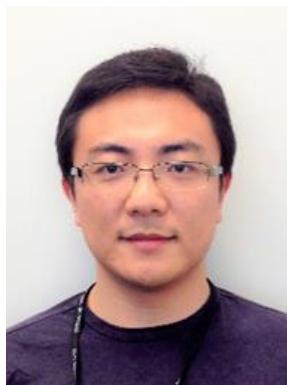


SOURCE SIZE AND EMITTANCE MEASUREMENTS FOR LOW-EMITTANCE LIGHT SOURCES

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Advanced Photon Source



Paul Scherrer Institut
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Canadian Light Source



Canadian Light Source



University of Saskatchewan
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Motivation

- New generation light sources with low emittance
 - High degree of coherence: coherent diffraction imaging, ptychography, XPCS etc.
 - Small beam: nano-focusing
 - High flux density

- MBA Lattice

$$\varepsilon \propto \frac{E^2}{(N_s N_d)^3}$$

E : electron beam energy

N_s : number of sectors in the ring

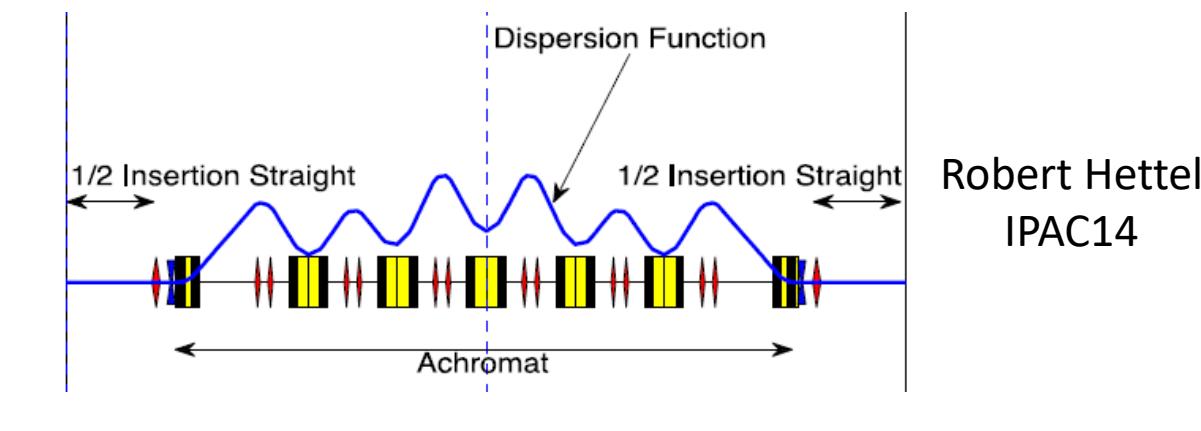
N_d : number of dipoles per sector

$$\varepsilon_y \propto \sigma_y \sigma'_y$$

σ : electron source size

σ' : electron source divergence

- Source size and beam stability measurements are challenging and important



	APS-U BM	SLS-2 BM	CLS-2 BM
σ_x (μm)	10.9	8	8.9
σ'_x (μrad)	20.6	28	7.7
σ_y (μm)	4.4	7	3.9
σ'_y (μrad)	4.4	1	0.8

Methods of measuring the source size

Imaging-based methods

- **Pinhole imaging**
- Coded aperture
- Compound refractive lenses
- Fresnel zone plates
- Kirkpatrick-Baez mirrors
- π polarization

Interference-based methods

- **Double-slit interferometry**
- **Grating interferometry**
- X-ray (multi/lens) interferometry
- π polarization with diffraction obstacle

Theoretical study

- N. Samadi, X. Shi, L. Dallin, and D. Chapman, "Source size measurement options for low-emittance light sources" Phys. Rev. Accel. Beams 23, 024801 (2020).
- N. Samadi presentation at IPAC20

Experimental study

- X. Shi, N. Samadi, L. Dallin, L. Assoufid, and D. Chapman, "Experimental comparison and calibration of three methods to measure electron source properties for synchrotron radiation," (2020) to be submitted.

Something different: ps-BPM system

- N. Samadi, "A real time phase space beam size and divergence monitor for synchrotron radiation" (PhD dissertation, University of Saskatchewan, 2019).
- N. Samadi, X. Shi, L. Dallin, and D. Chapman, Phys. Rev. Accel. Beams 23, 024801 (2020).
- N. Samadi, X. Shi, L. Dallin, and D. Chapman, Phys. Rev. Accel. Beams 22, 122802 (2019).
- N. Samadi, X. Shi, and D. Chapman, J. Synchrotron Radiat. 26, 1863 (2019).
- N. Samadi, X. Shi, L. Dallin, and D. Chapman, J. Synchrotron Radiat. 26, 1213 (2019).
- N. Samadi, X. Shi, L. Dallin, and D. Chapman, Proc. 10th Int. Part. Accel. Conf. FRXXRLS3, 4376 (2019).
- N. Samadi, L. Dallin, and D. Chapman, Proc. IBIC2018 186 (2018).
- N. Samadi, B. Bassey, M. Martinson, G. Belev, L. Dallin, M. De Jong, and D. Chapman, J. Synchrotron Radiat. 22, 946 (2015).

Pinhole Imaging

- $\Sigma^2 = (M\sigma_y)^2 + \sigma_{\text{pinhole}}^2 + \sigma_{\text{detector}}^2$

- Minimize $\frac{\sigma_{\text{pinhole}}}{M\sigma_y}$

- Method 1: Analytical

- $\sigma_{\text{pinhole}}^2 = \sigma_{\text{geo}}^2 + \sigma_{\text{diff}}^2$

with $\sigma_{\text{geo}} = \frac{a}{2\sqrt{3}} \frac{(p+q)}{p}$, $\sigma_{\text{diff}} = \frac{0.886}{2.355} \frac{\lambda q}{a}$

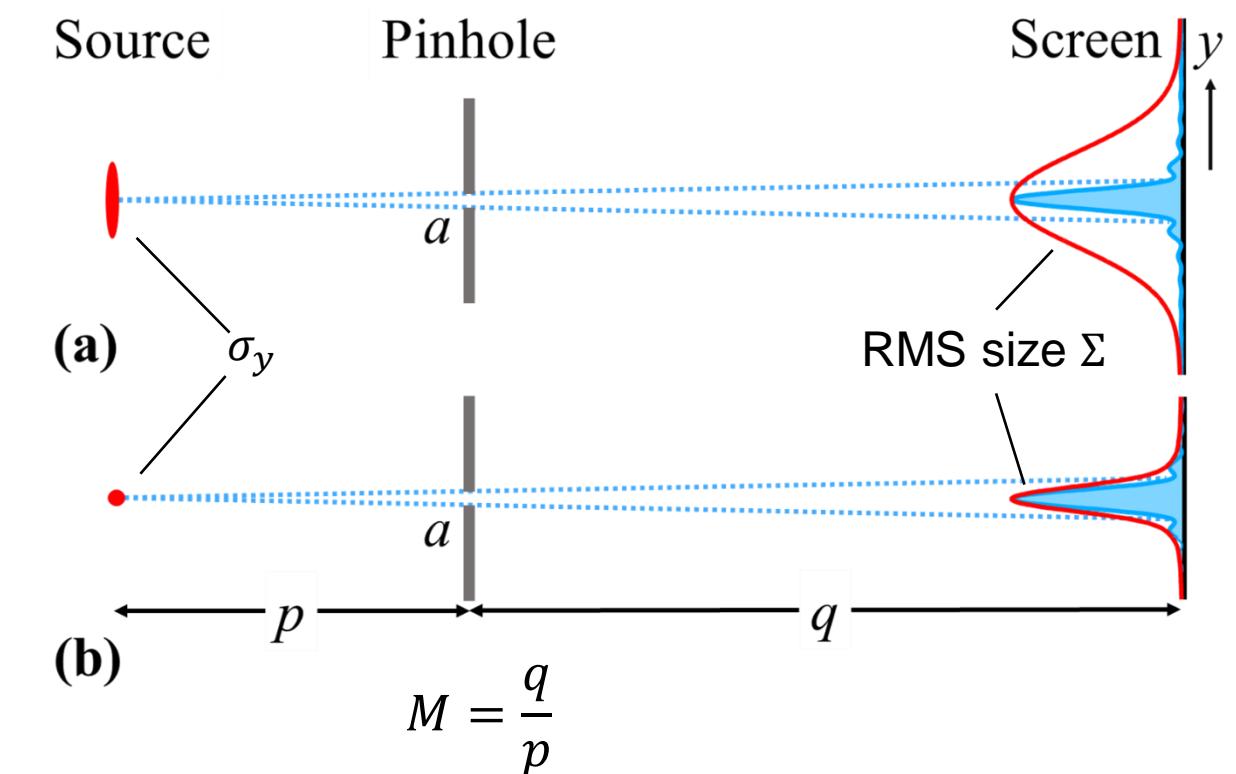
- $\left(\frac{\sigma_{\text{pinhole}}}{M\sigma_y} \right)_{\min} = \frac{1}{\sigma_y} \sqrt{0.217\lambda \left(p + \frac{p^2}{q} \right)}$

- Method 2: Near field (NF) propagation

- $I_s(y) = \varepsilon(y) \cdot \varepsilon^*(y)$

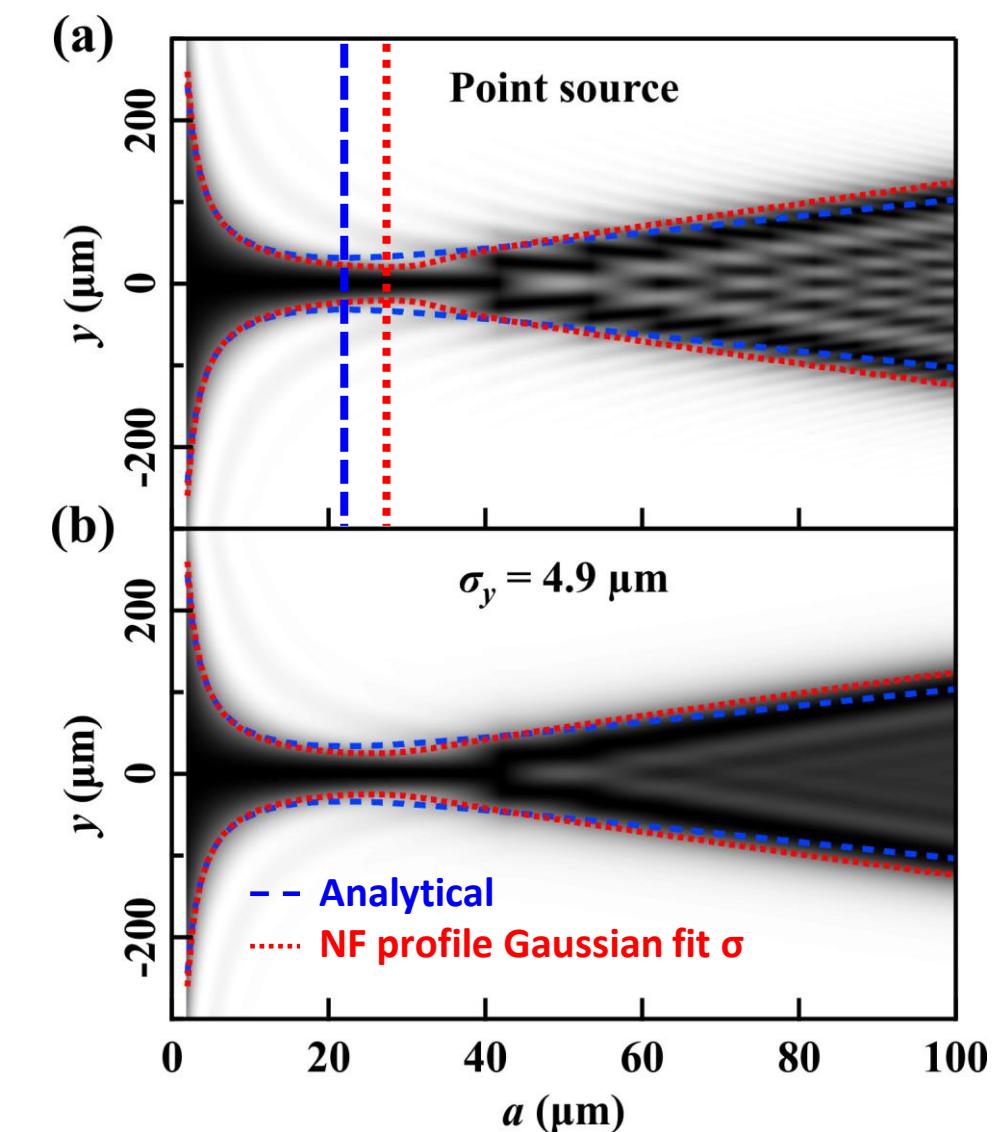
- $\varepsilon(y) = \frac{1}{i\lambda q} \int_{-a/2}^{a/2} \varepsilon_0(y_0) \exp \left[\frac{i\pi}{\lambda q} (y - y_0)^2 \right] dy_0$

- $I_G = I_s(y) \otimes \left[\exp \left(-\frac{y^2 p^2}{2\sigma_y^2 q^2} \right) \right]$



Pinhole Imaging: optimization

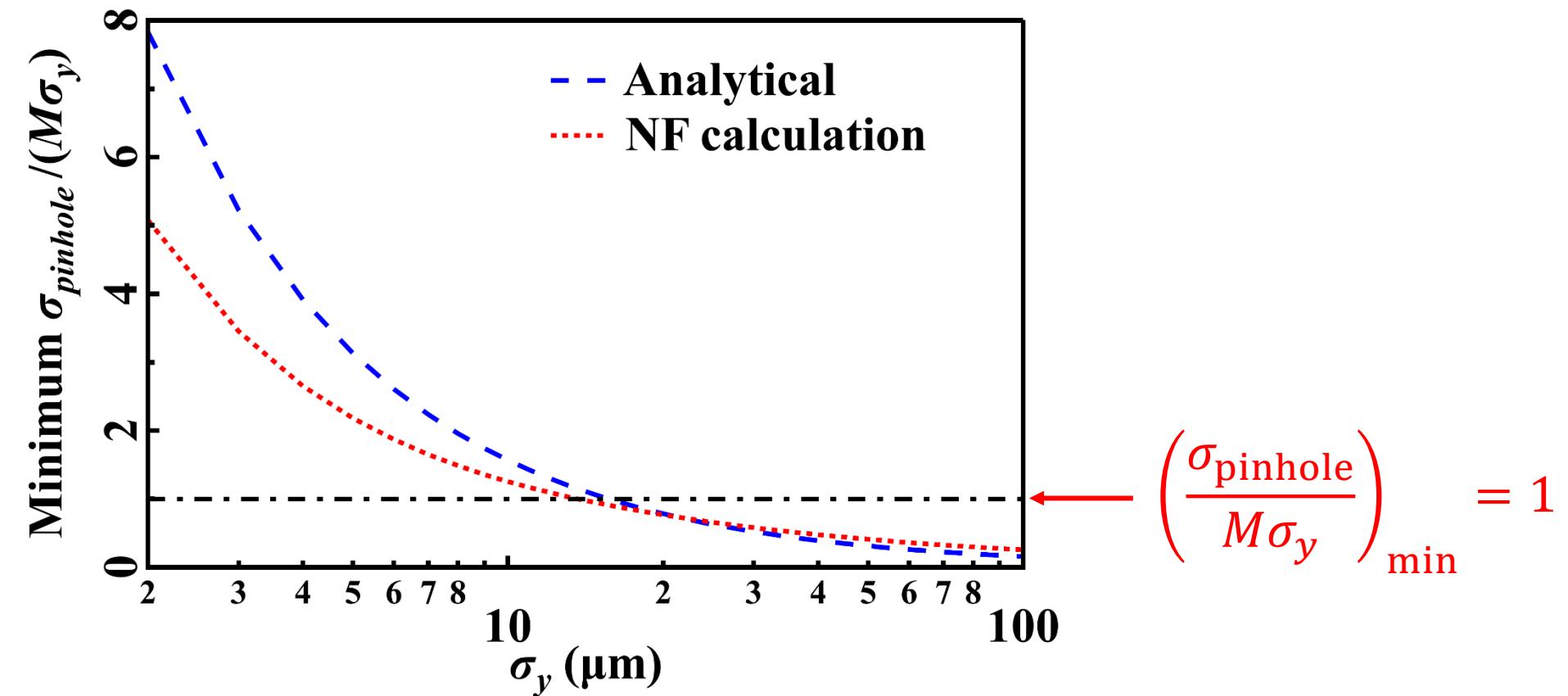
- $\Sigma^2 = (M\sigma_y)^2 + \sigma_{\text{pinhole}}^2 + \sigma_{\text{detector}}^2$
- Minimize $\frac{\sigma_{\text{pinhole}}}{M\sigma_y}$
- Method 1: Analytical
 - $\sigma_{\text{pinhole}}^2 = \sigma_{\text{geo}}^2 + \sigma_{\text{diff}}^2$
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 - $\left(\frac{\sigma_{\text{pinhole}}}{M\sigma_y}\right)_{\min} = \frac{1}{\sigma_y} \sqrt{0.217 \lambda \left(p + \frac{p^2}{q}\right)}$
- Method 2: Near field (NF) propagation
 - $I_s(y) = \varepsilon(y) \cdot \varepsilon^*(y)$
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 - $I_G = I_s(y) \otimes \left[\exp\left(-\frac{y^2 p^2}{2\sigma_y^2 q^2}\right)\right]$



$\lambda = 0.827 \text{ Å}$ (photon energy, $E = 15 \text{ keV}$)
 $p = 6.6 \text{ m}$, $q = 13.4 \text{ m}$, APS-U M3 source

Pinhole Imaging: limitation

- Optimized aperture size for different source sizes
 - Limited resolution  difficult to measure source sizes < 10 micron



Pinhole Imaging: summary

	Pinhole Imaging
Optical setup	Simple, aberration free
Measurement directions	All
Fast measurement	Yes, white beam
Resolution	Limited to $>10 \mu\text{m}$
High-resolution detector	Yes
Optics fabrication	Hard
Information	Size and position

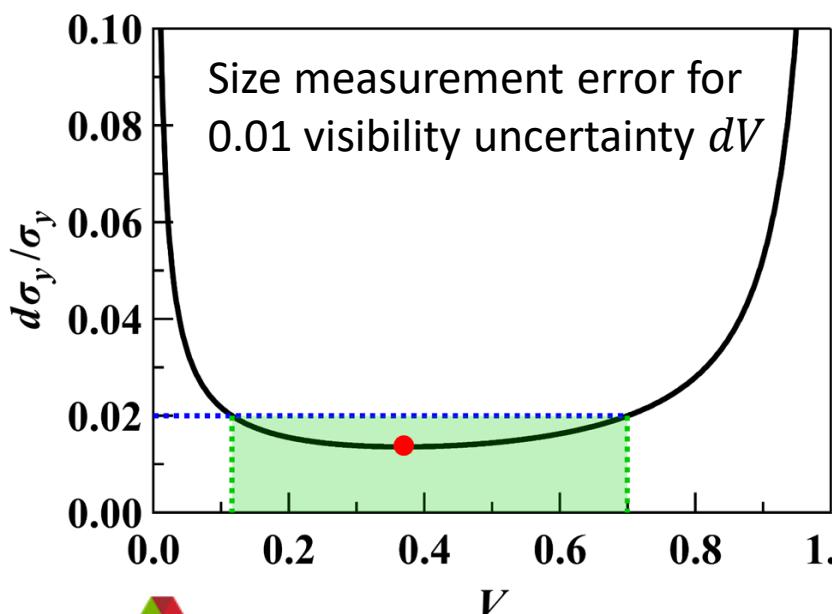
Double-Slit Interferometry

- $I = 2I_0 \operatorname{sinc}^2\left(\frac{\pi a}{\lambda q} y\right) \left[1 + V \cos\left(\frac{2\pi d}{\lambda q} y\right)\right]$

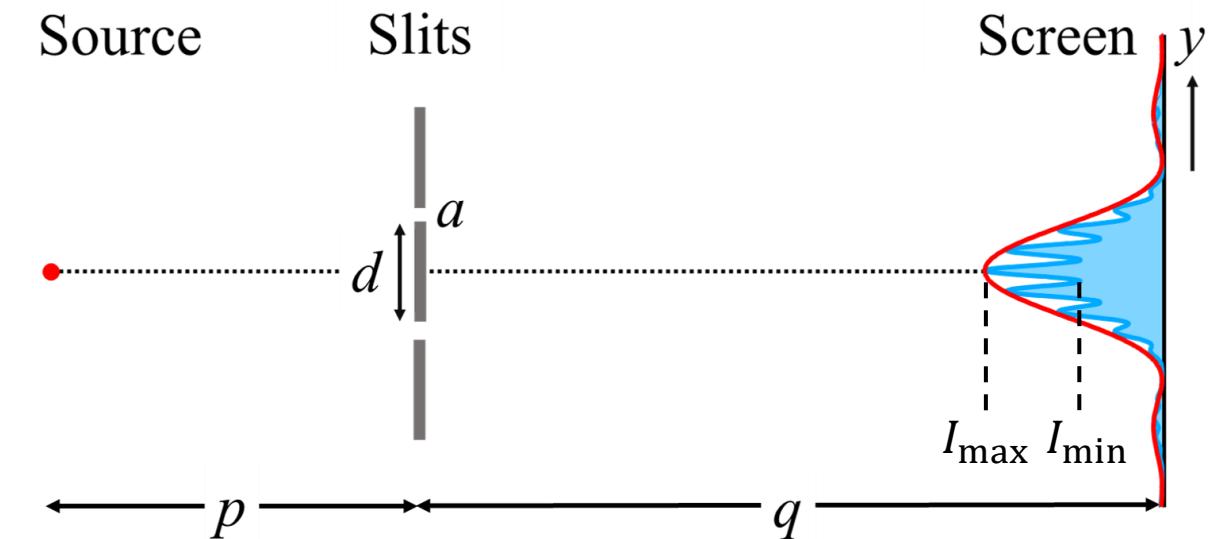
- Gaussian source

$$\sigma_y = \frac{\lambda p}{\pi d} \sqrt{\frac{1}{2} \ln \frac{1}{V}} \quad \rightarrow \quad \frac{d\sigma_y}{\sigma_y} = \frac{|dV|}{2V \ln \frac{1}{V}}$$

- Minimize the source size sensitivity $\frac{d\sigma_y}{\sigma_y}$



- Minimum $d\sigma_y/\sigma_y$ at $V = 0.37$
- To ensure 2% sensitivity of source size measurement, the required visibility range $0.12 < V < 0.70$



$$V = \frac{I_{\max} - I_{\min}}{I_{\max} + I_{\min}}$$

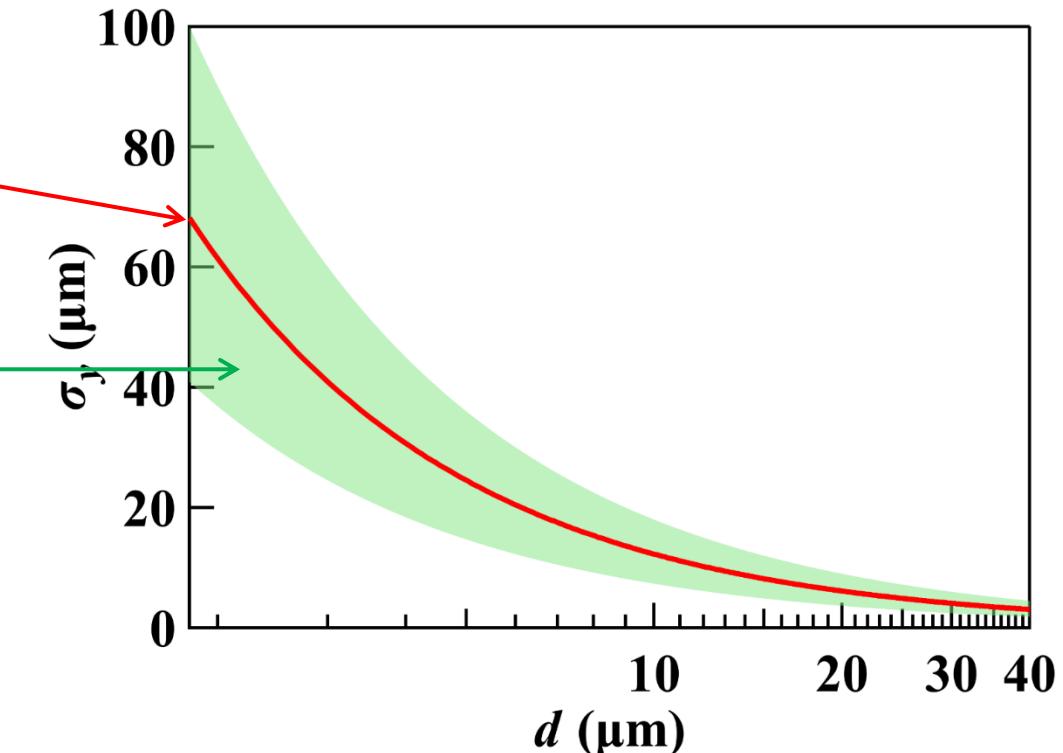
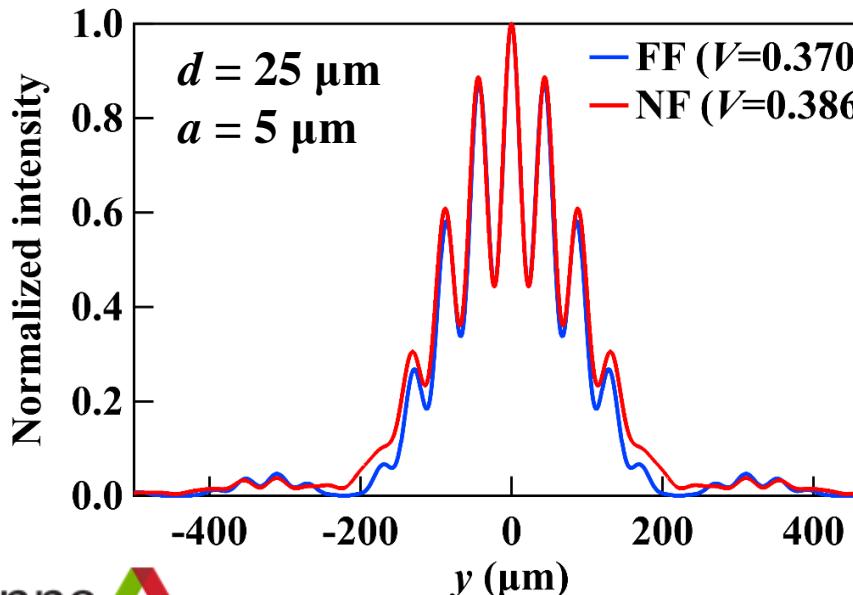
Double-Slit Interferometry: optimization

■ Slit separation d study

- Optimized at size ($V = 0.37$) $\sigma_y = 0.225 \frac{\lambda p}{d}$
- Detectable size range with at least 2% sensitivity ($0.12 < V < 0.70$):

$$0.13 \left(\frac{\lambda p}{d} \right) < \sigma_y < 0.33 \left(\frac{\lambda p}{d} \right)$$

■ Slit size a study

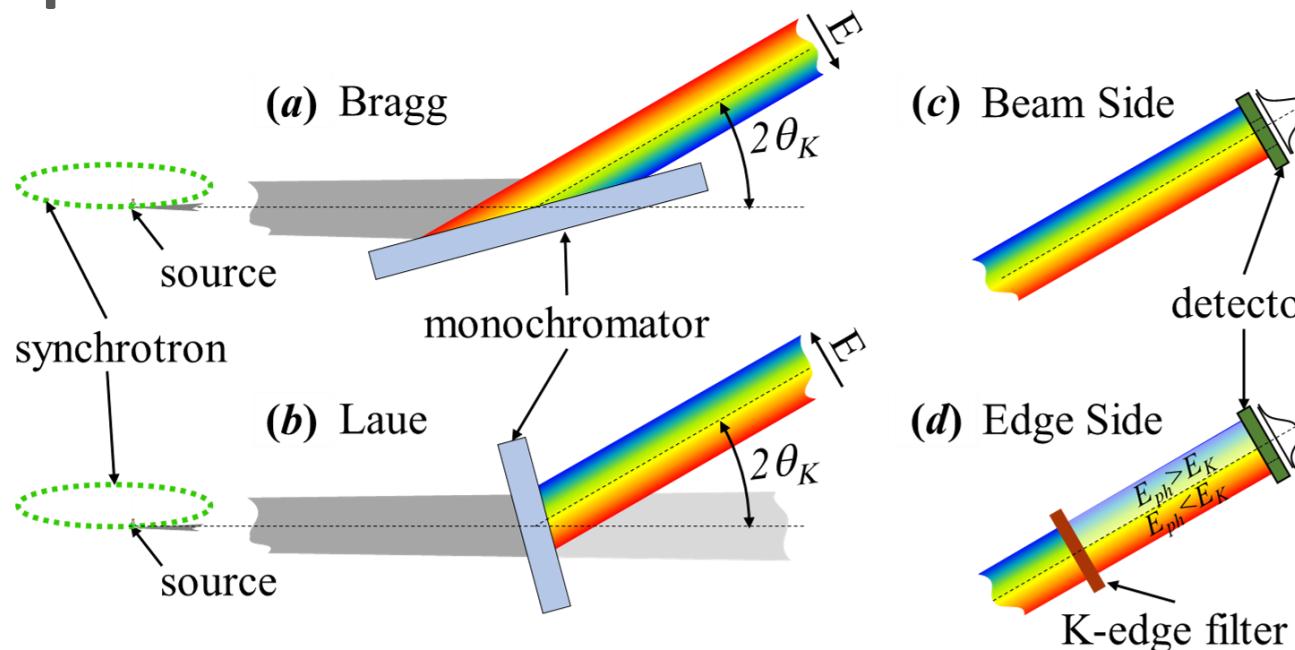


- a needs to be small enough ($< d/5$) to ensure far-field approximation is valid
- Larger a , higher flux density

Double-Slit Interferometry: summary

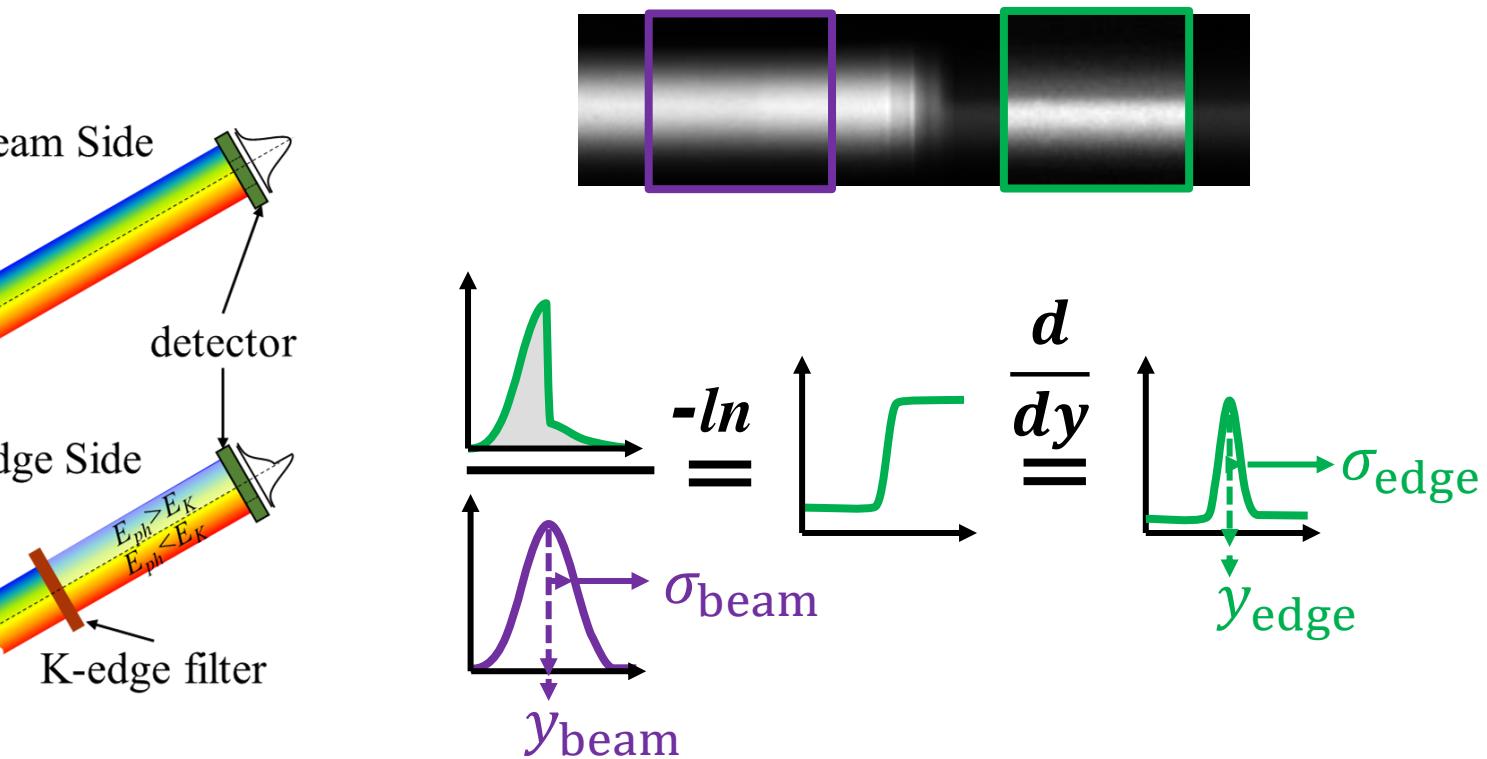
	Pinhole Imaging	Double Slit Interferometry
Optical setup	Simple, aberration free	Require monochromator
Measurement directions	All	1-D
Fast measurement	Yes, white beam	No
Resolution	Limited to $>10 \mu\text{m}$	Highest
High-resolution detector	Yes	Yes
Optics fabrication	Hard	Hard
Information	Size and position	Size only

ps-BPM



$$y = y_{\text{edge}}$$

$$y' = \frac{y_{\text{beam}} - y_{\text{edge}}}{D}$$



$$\sigma_y = \sqrt{\sigma_{\text{edge}}^2 - (D\sigma_{y'_{K-\text{edge}}})^2 - (D\sigma_{y'_{\text{mono}}})^2}$$

$$\sigma_{y'} = \frac{1}{D} \sqrt{\sigma_{\text{beam}}^2 - \sigma_y^2 - (D\sigma_{y'_{\text{Ph}}})^2}$$

ps-BPM: optimization

- $\sigma_{IRF} = D\sigma_{y'_{\text{total}}} = D \sqrt{\sigma_{y'_{\text{mono}}}^2 + \sigma_{y'_{K-\text{edge}}}^2}$

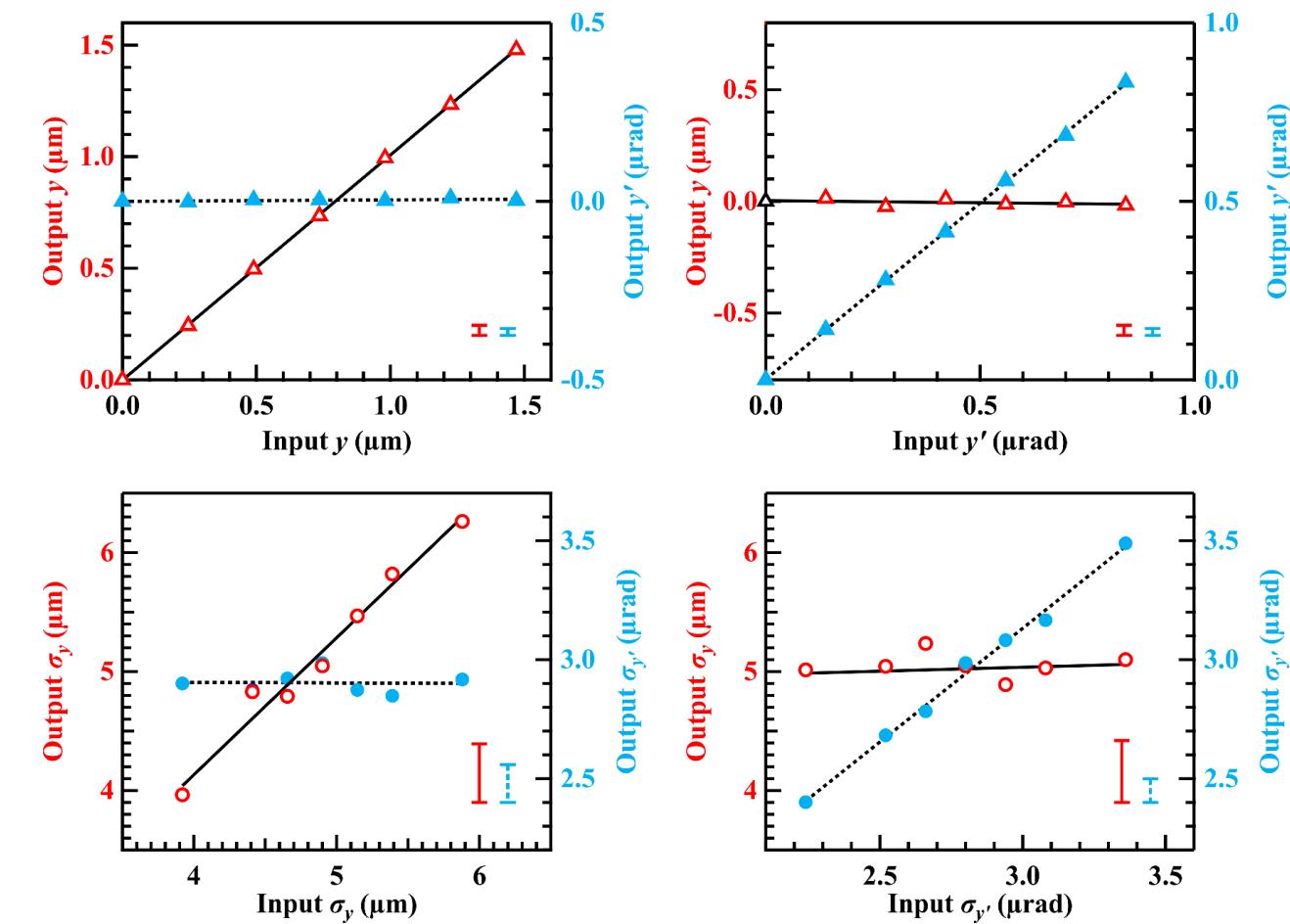
- Small source-to-detector distance, D
- Effect dominated by the angular projected K -edge width

$$\sigma_{y'_{K-\text{edge}}} = \frac{\tan \theta_K}{E_K} \sigma_{E_{K-\text{edge}}}$$

- Small $\sigma_{E_{K-\text{edge}}}$
- Large E_K
- Small θ_K (low reflection index)

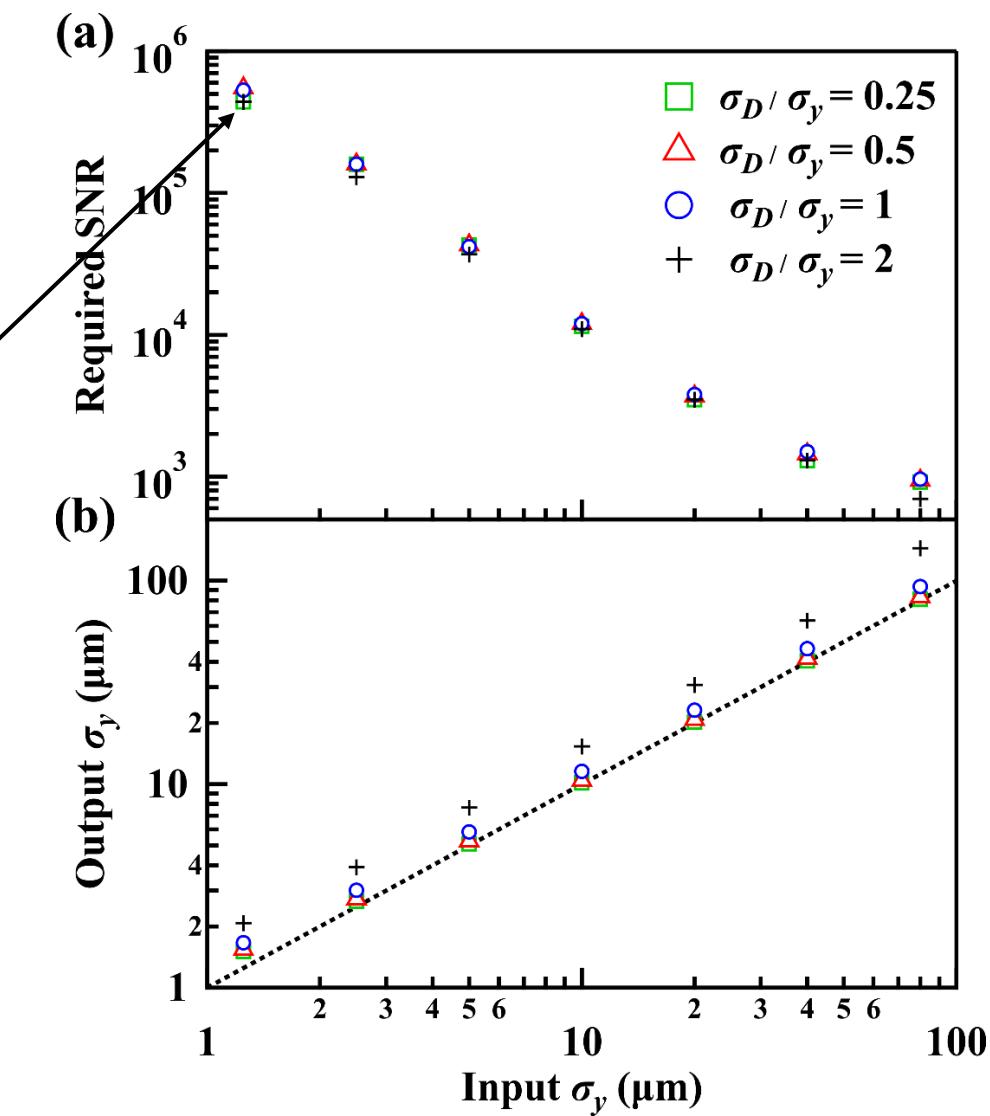
Shadow simulation of ps-BPM for APS-U Source

- Si (111) single Bragg, Barium K-edge (37.441 keV)
- $D = 10$ m, detector resolution 10 μm



ps-BPM: optimization

- Resolution of the ps-BPM relies on photon flux and noise level (SNR)
- SNR determined by
 - Dark noise of the detector
 - Fluorescence from the K-edge filter
 - Compton scattering from the monochromator crystals
 - Single Bragg (SNR = 6700) at 6.6 m, detector at 10 m.
- Improve SNR by
 - Summing up N_h pixels in the horizontal direction: $N_h=1000$
 - Averaging over N_i images: $N_i=8$
 - Improve SNR by $\sqrt{N_h N_i}$
 - Single Bragg: SNR = 6×10^5



Ps-BPM: summary

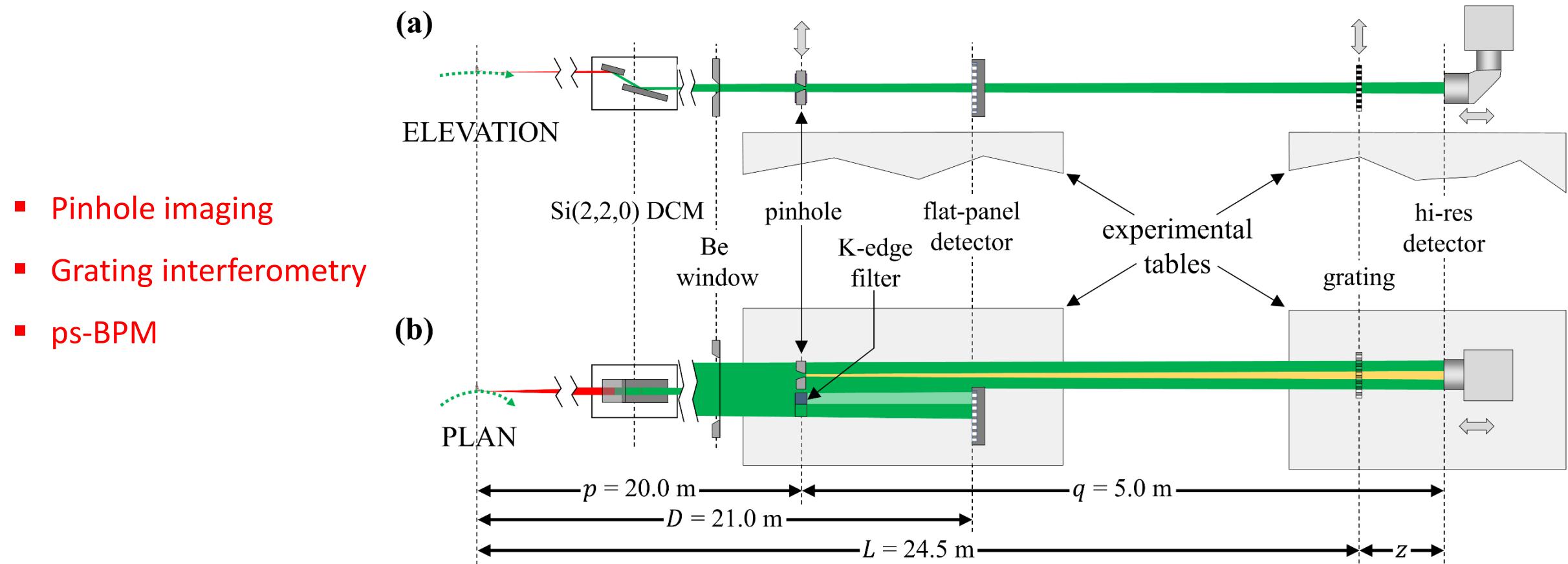
	Pinhole Imaging	Double Slit Interferometry	ps-BPM
Optical setup	Simple, aberration free	Require monochromator	Require monochromator
Measurement directions	All	1-D	1-D in mono diffraction plane
Fast measurement	Yes, white beam	No	yes y, y' , not small σ_y, σ'_y
Resolution	Limited to $>10 \mu\text{m}$	Highest	High, but needs calibration
High-resolution detector	Yes	Yes	No
Optics fabrication	Hard	Hard	Easy
Information	Size and position	Size only	$y, y', \sigma_y, \sigma'_y$ simultaneously

Comparison of three methods (theory)

	Pinhole Imaging	Double Slit Interferometry	ps-BPM
Optical setup	Simple, aberration free	Require monochromator	Require monochromator
Measurement directions	All	1-D	1-D in mono diffraction plane
Fast measurement	Yes, white beam	No	yes y, y' , not small σ_y, σ'_y
Resolution	Limited to $>10 \mu\text{m}$	Highest	High, but needs calibration
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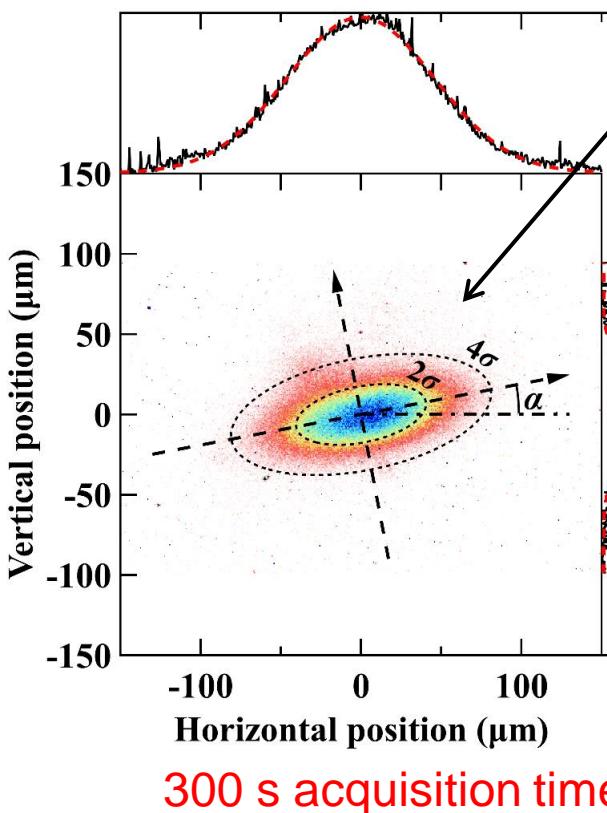
Experimental comparison of three methods

- Electron source size measurement at the BMIT beamline at the Canadian Light Source



Experimental comparison of three methods

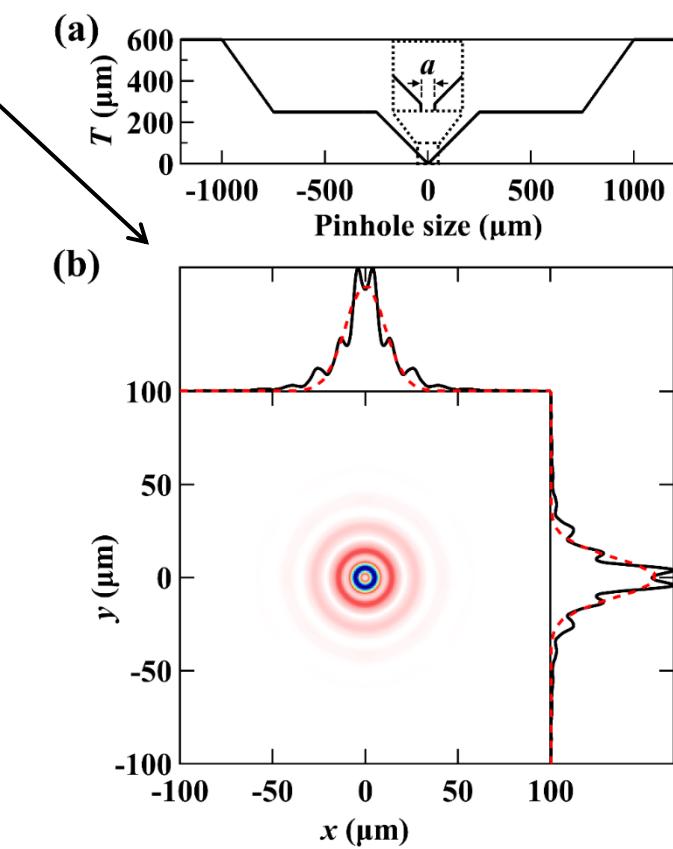
- Pinhole imaging, 20 keV



$$\sigma_{\text{image},x,y}^2 = M^2 \sigma_{\text{source},x,y}^2 + \sigma_{\text{pin}}^2 + \sigma_{\text{det}}^2 \longrightarrow \text{Neglected}$$

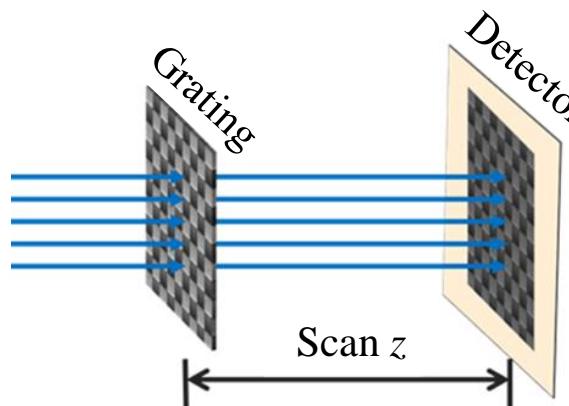
$$I(x,y) = I_0 \exp \left[- \left(\frac{\cos^2 \alpha}{2\sigma_{\text{image},x}^2} + \frac{\sin^2 \alpha}{2\sigma_{\text{image},y}^2} \right) x^2 - \left(\frac{\sin 2\alpha}{4\sigma_{\text{image},x}^2} - \frac{\sin 2\alpha}{4\sigma_{\text{image},y}^2} \right) xy - \left(\frac{\sin^2 \alpha}{2\sigma_{\text{image},x}^2} + \frac{\cos^2 \alpha}{2\sigma_{\text{image},y}^2} \right) y^2 \right]$$

$\sigma_{\text{source},x}$ (μm)	$\sigma_{\text{source},y}$ (μm)	α (°)
160±3	60±3	11.4±0.5



Experimental comparison of three methods

- Grating interferometry, 20 keV



$$x = \frac{z\lambda}{p_x}$$

$$y = \frac{z\lambda}{p_y}$$

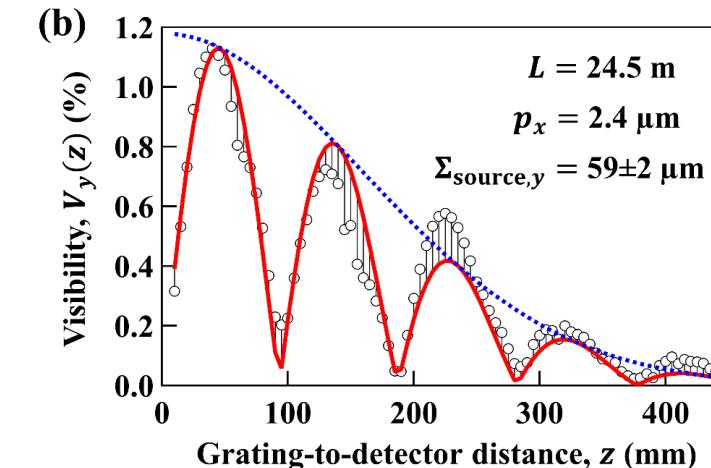
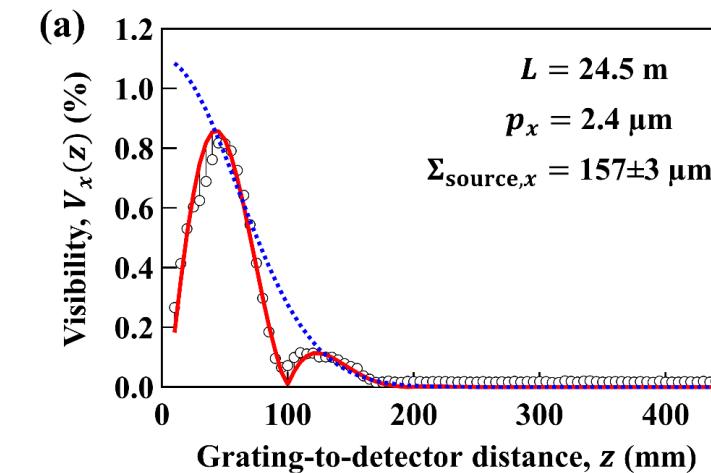
$$V_{x,y}(z) = A_{x,y} \left| \sin \left[\frac{\pi \lambda z L}{p_{x,y}^2 (L+z)} \right] \right| \exp \left[\frac{-2\pi^2 z^2 \Sigma_{\text{source},x,y}^2}{p_{x,y}^2 (L+z)^2} \right]$$

$A_{x,y}$ — scaling parameter

$p_{x,y}$ — period of grating pattern

L — source-to-grating distance

$\Sigma_{\text{source},x,y}$ — projected source size



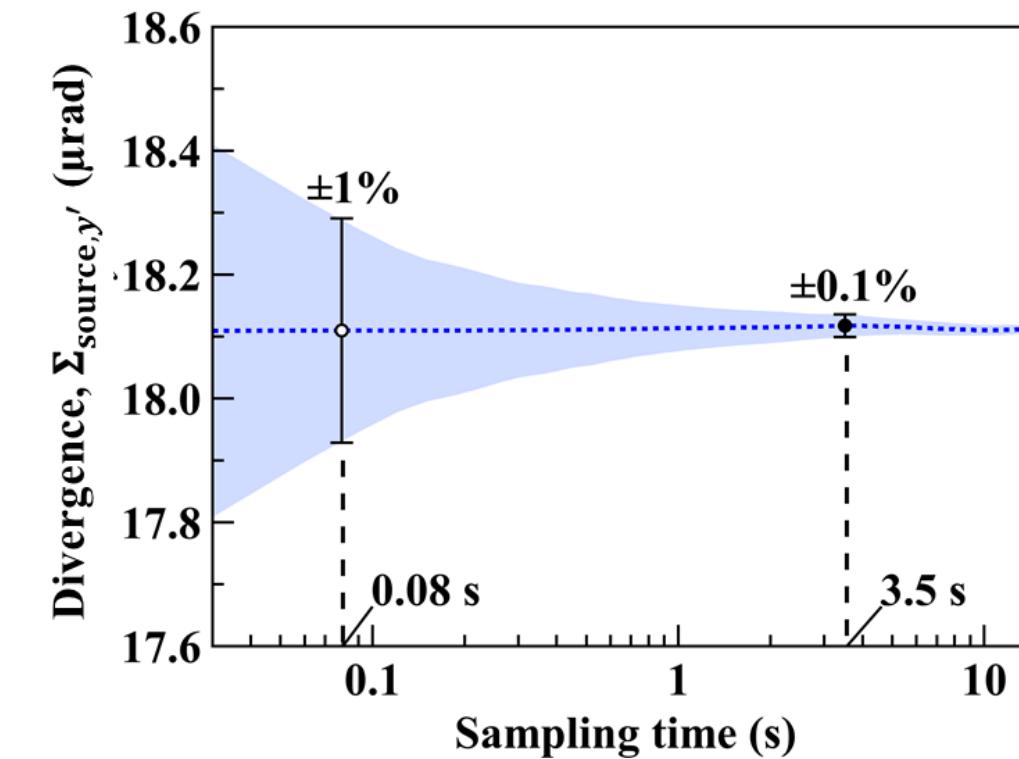
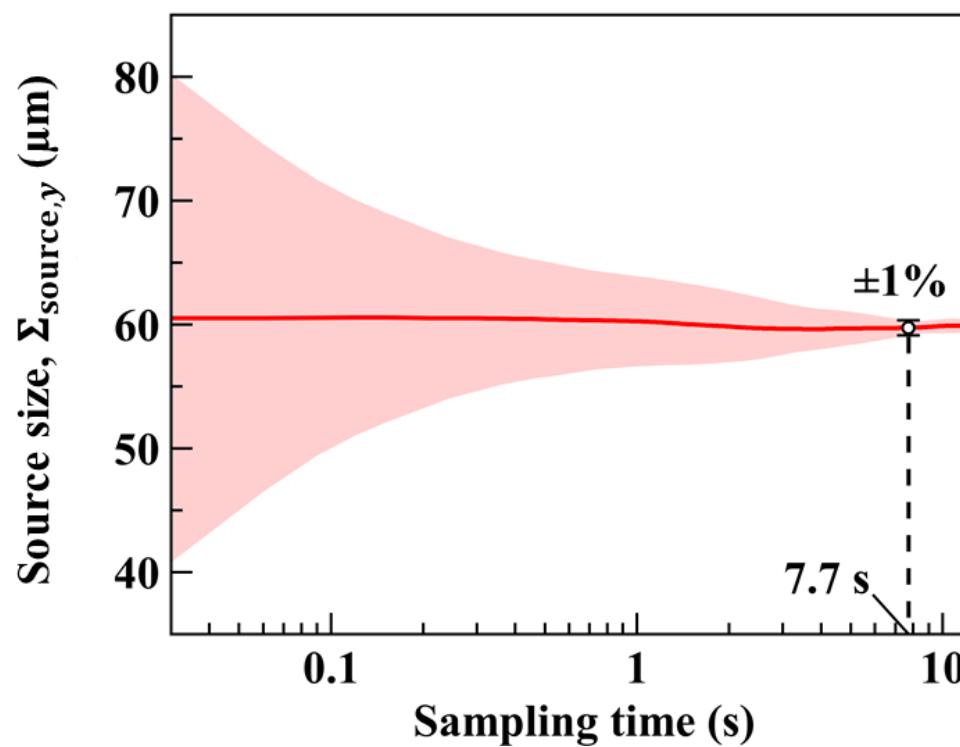
S. Marathe, X. Shi, M. J. Wojcik, N. G. Kujala, R. Divan, D. C. Mancini, A. T. Macrander, and L. Assoufid, Opt. Express **22**, 14041 (2014).

Technique	$\Sigma_{\text{source},x}$ (μm)	$\Sigma_{\text{source},y}$ (μm)
Grating	157 ± 3	59 ± 2
Pinhole	155 ± 3	61 ± 2

60 s per image, 2 hours total

Experimental comparison of three methods

- ps-BPM calibration, Ba K-edge at 37.441 keV
 - σ_{IRF} is set to match $\Sigma_{source,y} = 60$ from pinhole and grating measurements



Conclusion

- Three radiation-based methods for source size measurement were reviewed.
- They can provide complementary information.
 - Pinhole imaging provides 2-D imaging of the source.
 - Double-slit or grating interferometry provide high-resolution for measuring small source sizes
 - ps-BPM after calibration can provide real-time information on source position, angle, size, and divergence simultaneously.
- New facilities should consider combining multi-methods at a dedicated diagnostic beamline (normally bending magnet).
- Challenges:
 - ps-BPM works better at high energies while the other two methods prefer lower energies
 - Application to undulators and FELs
 - Studies are being carried out to solve these challenges.

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Thank you!